

Wafer Level Package Technology Applied to System Packaging

Takeshi Wakabayashi
(Casio Computer/Japan)

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Wafer Level Package Technology Applied to System Packaging

“WLP and EWLP®” as a new “JISSO” Technology

TAKESHI WAKABAYASHI

General Manager

Advanced Packaging Technology Dep.

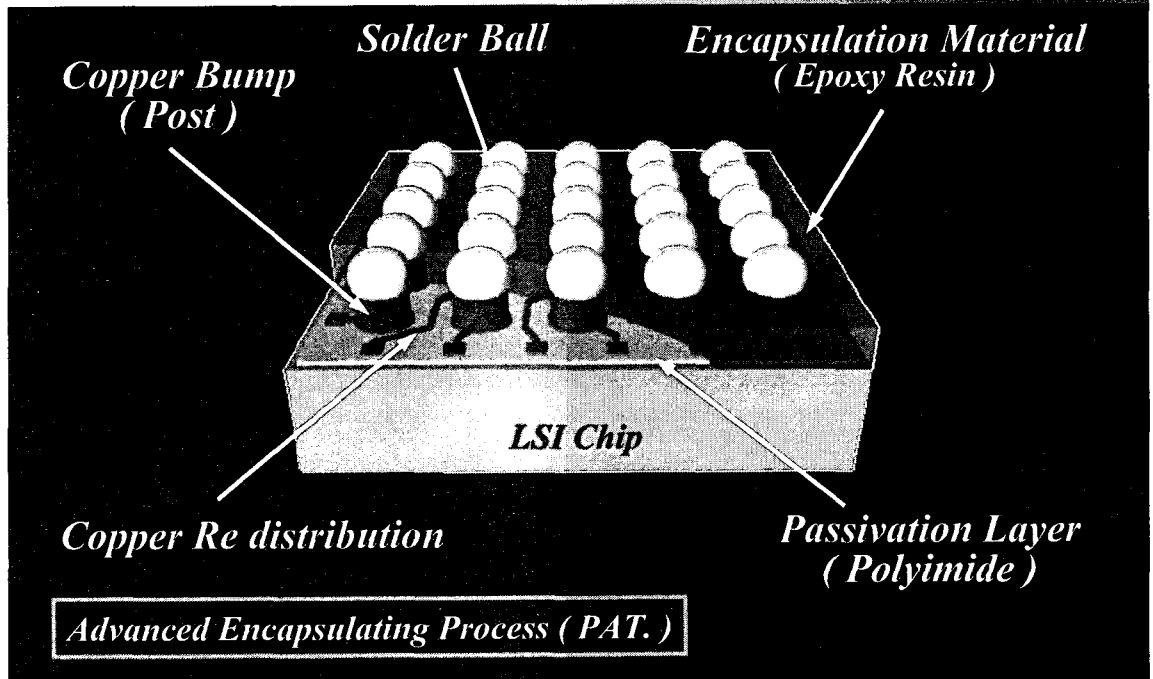
Core Technologies R&D Division

CASIO COMPUTER CO., LTD.

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Basic Structure of WLP

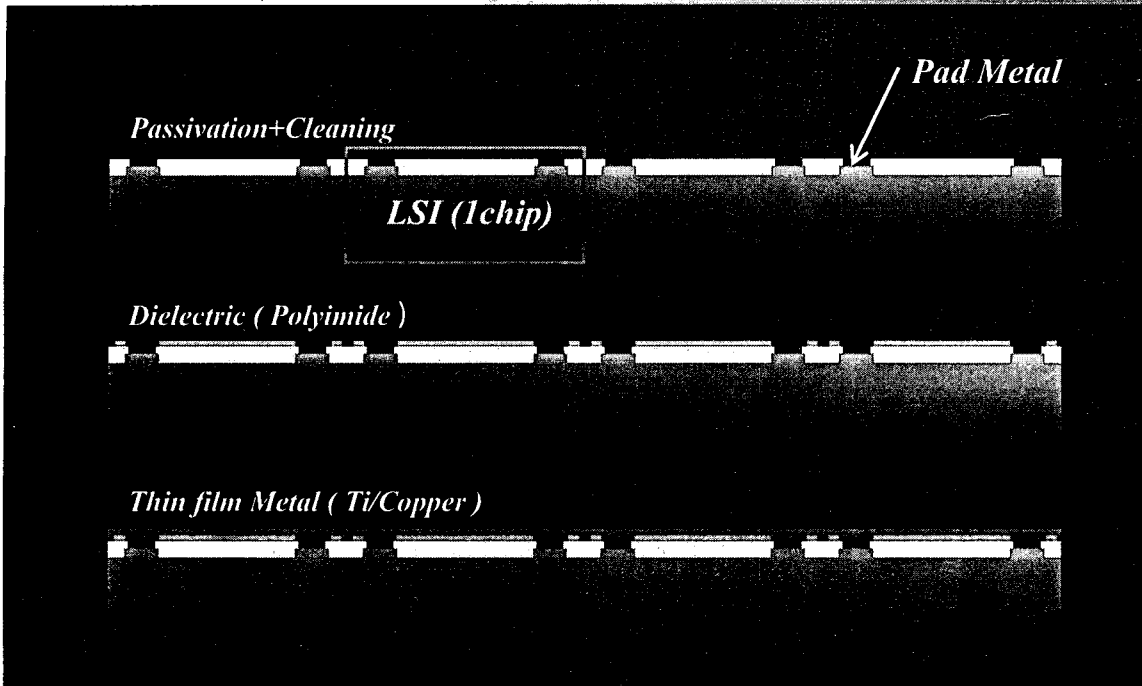
Page 3



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WLP Process Flow "Thin film"

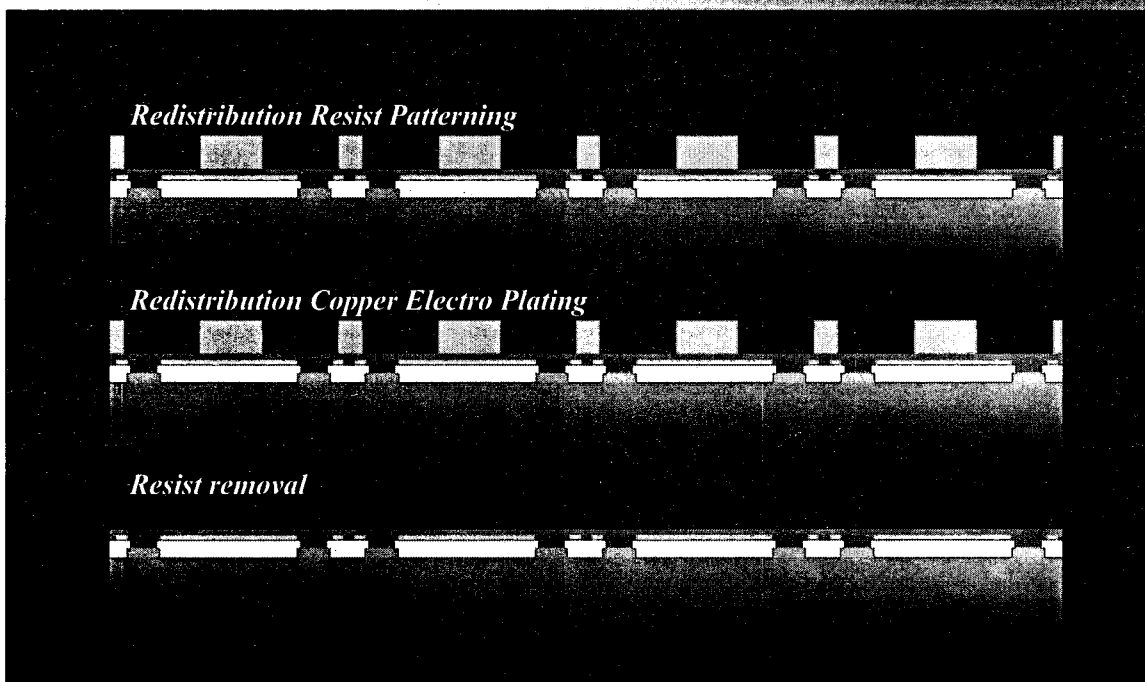
Page 5



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WLP Process Flow "Re distribution"

Page 6



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WLP Process Flow "Copper Post"

Page 7

Post Resist Patterning



Post Copper Electro Plating

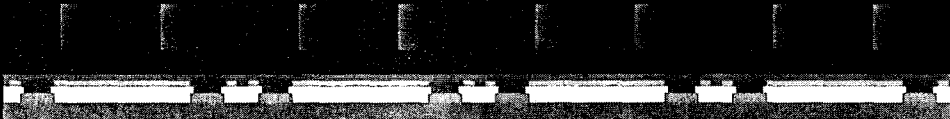


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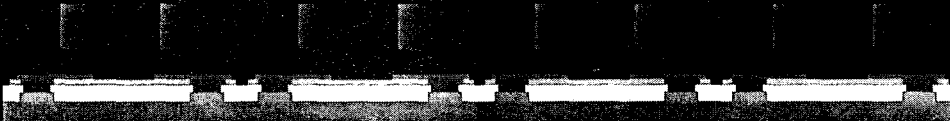
WLP Process Flow "Copper Post"

Page 8

Resist Removal



Thin film Metal Etching

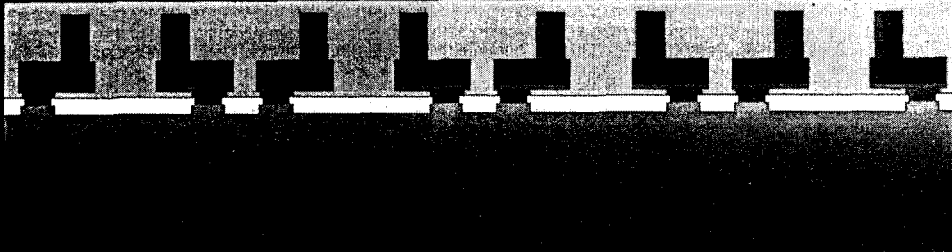


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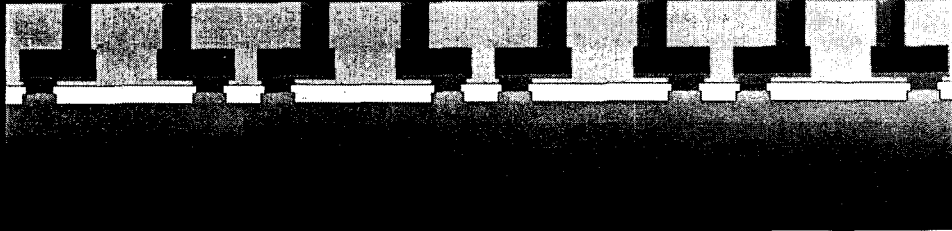
WLP Process Flow "Encapsulation"

Page 9

Encapsulating (Liquid Epoxy Material)



Surface Grinding (Copper post & Encapsulating Material)



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WLP Process Flow "Solder Ball & Dicing"

Page 10

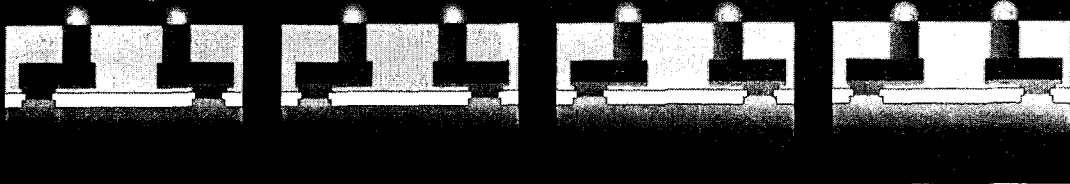
Back side Grinding & Laser Marking



Terminal Solder Ball Placement



Dicing



Solder Ball Placement Technology

- *Transfer using Vacuum Plate*
- *Ball drop using Metal Mask*
- *Ball drop in Liquid Condition*
 - *Direct Drop using Temp. Mask*
 - *Transfer*

Reliability Data

<i>Moisture Sensitivity</i>	<i>JEDEC Level 1@260 °C 85 °C/85%RH/168hours, 10 times</i>
<i>Temp Cycle</i>	<i>-65 °C/+150 °C, 2000 cycles</i>
<i>High Temp Storage</i>	<i>150 °C, 2000 hours</i>
<i>Temp Humidity Bias</i>	<i>85 °C/85%RH/10V,L/S=10/10um, 2000 hours</i>
<i>HAST</i>	<i>130 °C/85%RH/10V,L/S=10/10um, 168 hours</i>
<i>PCT</i>	<i>121 °C/2atm, 500 hours</i>
<i>Temp Cycle on PCB</i>	<i>-25 °C/+125 °C, 900 cycles (7x7 array, 0.5mmpitch, 0.1% failure)</i>

Advantages of CASIO's WLP

- **Basic Characteristic WLP**
 - High Yield, Performance and Reliability
 - High Productivity and Low Cost
 - Easy to use
 - 300mm Wafer Processing
 - Advanced Encapsulating Process (US PAT.) & Material
- **Low Cost Solution for Test Process**
 - Handling Cost
 - Wafer Level B/I
- **EWLP® Technology Solution**
 - High Performance Module
- **Stress Buffer (Leading-Edge Semiconductor)**
 - 90nm, 65nm, 45nm
 - Low/High-k Materials

Perfect Protection
SMT Compatible
High Productivity

Reliable Low Cost Contact
Protect against Mechanical Damage

High Performance System
Solder Less Module

High Performance Device Solution

WLP Structure & Process (Simple Ball vs. Copper Post)



1. First dielectric layer
2. Photo pattern
3. Sputter UBM
4. Photo resist pattern
5. Etch to form trace and pad
6. Second dielectric layer
7. Photo pattern
8. Attach pre-formed solder ball
9. Reflow solder

1. First dielectric layer
2. Photo pattern
3. Sputter UBM
4. Photo resist pattern
5. Copper electroplate
6. Resist pattern
7. Copper electroplate
8. Etch UBM
9. Encapsulate
10. Grind
11. Attach pre-formed solder ball
12. Reflow solder

- Mechanical stress from ?**
- ✓ Package probe test, B/I
 - ✓ Handling, Taping
 - ✓ SMT Pick and Place
 - ✓ Under fill, Cure
 - ✓ Case Assembly
 - ✓ Product in Use
 - Operation
 - Vibration
 - Drop

High current distribute

Mechanical protect

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Shock Resistant Evaluation Result (Customer Test)

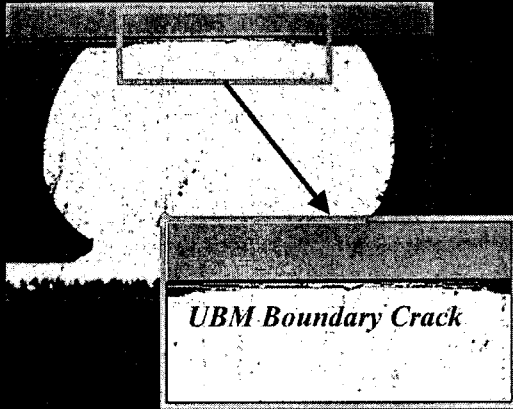
Page 16

- Shock (PCB Assembly without Underfill): 24,000 G
- No. of Sample Open Failure
- Solder Ball Type : 10 4
- Casio's WLP : 10 0
- (Same Size Daisy chain Sample)



SN*****

1.4 x 0.9 mm
0.5 mm pitch
5 Balls



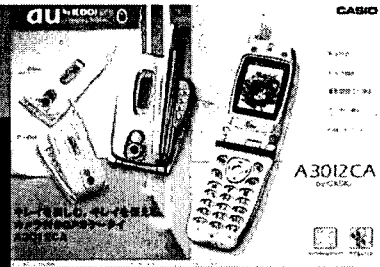
UBM Boundary Crack



Silicon Crack

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CMOS Camera Module in Cellular



A3012CA

Digital Signal Processor
WLP (4.24mm x 4.24mm)
0.4 mm pitch, 80 balls

Module Structure

CMOS Image Sensor

Back Side

Lens Unit

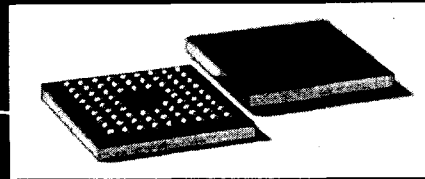
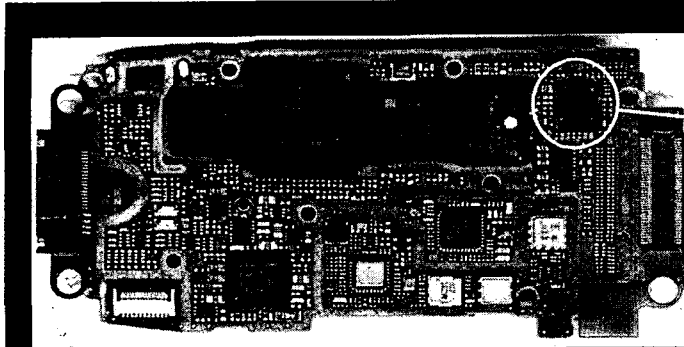
Back Side

DSP Assembly CMOS Sensor Assembly Lens Unit Assembly

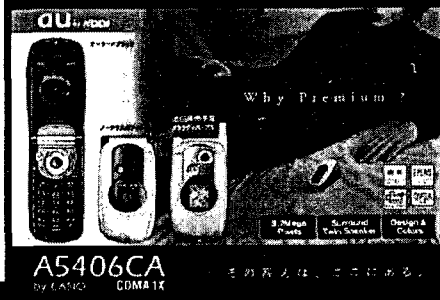
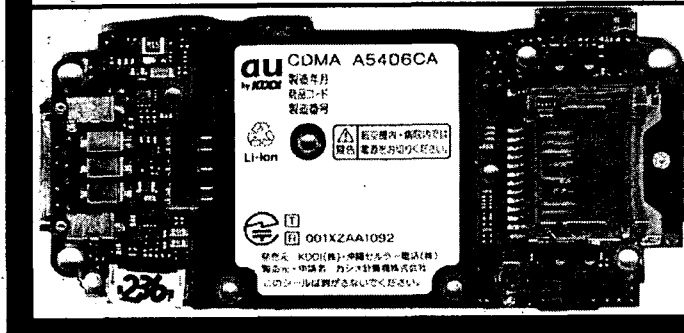
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A5406CA / au by CASIO

Page 21



YAMAHA MA-5Si
(YMU783)
5.41 x 5.26mm WLP
0.5mm pitch 73Balls



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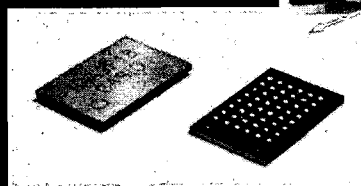
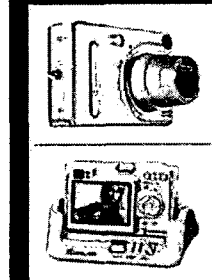
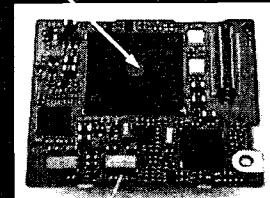
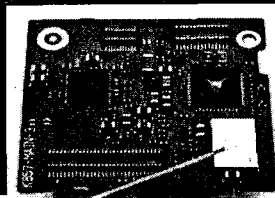
DSC Application : CASIO "Exilim Z4"

Page 24

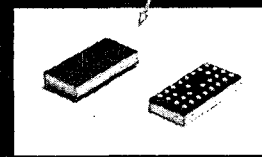


Main Processor Module

ASIC & 128Mb SDRAM
SiP (2 Chips Stack Type)
15 x 15 mm
0.65 mm pitch, 336 balls



128Mb Flash Memory
WLP (5.78 x 8.47 mm)
0.8 mm pitch, 48 balls



CCD V-Driver
WLP (2.21 x 4.35 mm)
0.5 mm pitch, 28 balls

- *Function of Electroplated Copper Line*
 - *Re-distribution Terminal*
 - *Inductor, Transformer*
 - *High Electric Current Line*
 - *High Speed Signal Line*
 - *Antenna*

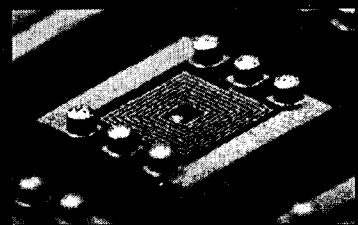
- *Thick Encapsulated Layer for Protection*
 - *Protection against Mechanical Stress*
 - *Embed into Organic Substrate*
 - *Stress Buffer for Low-k Materials*

- *Structure and Technology*
 - *Spiral Inductor by Electroplated Copper (Thickness: 5um-20um)*
 - *1 layer or 2 layers structure*

- *Purpose*
 - *Higher Q-factor than Thin Film Integrated Inductor*
 - *Smaller than Individual Inductor Device*

- *Application*
 - *Integration in RF chip*
 - *Power Device (DC-DC Converter)*

- *CASIO's Patent*



IV High Speed Signal Line

- *Structure and Technology*
 - *High Speed Signal Line by Electroplated Copper (Thickness: 5um-10um)*
 - *1 layer or 2layers structure : Depend on Net Numbers*
- *Purpose*
 - *High Speed Line (Clock, Signal)*
 - *Wide Band Bus Line*
 - *Power and Ground Line (Reduce Voltage Noise)*
 - *Global Electrical Connection between IP Block in Large System Chip*
- *Application*
 - *High Performance System LSI, CPU, GPU*

Super Connect

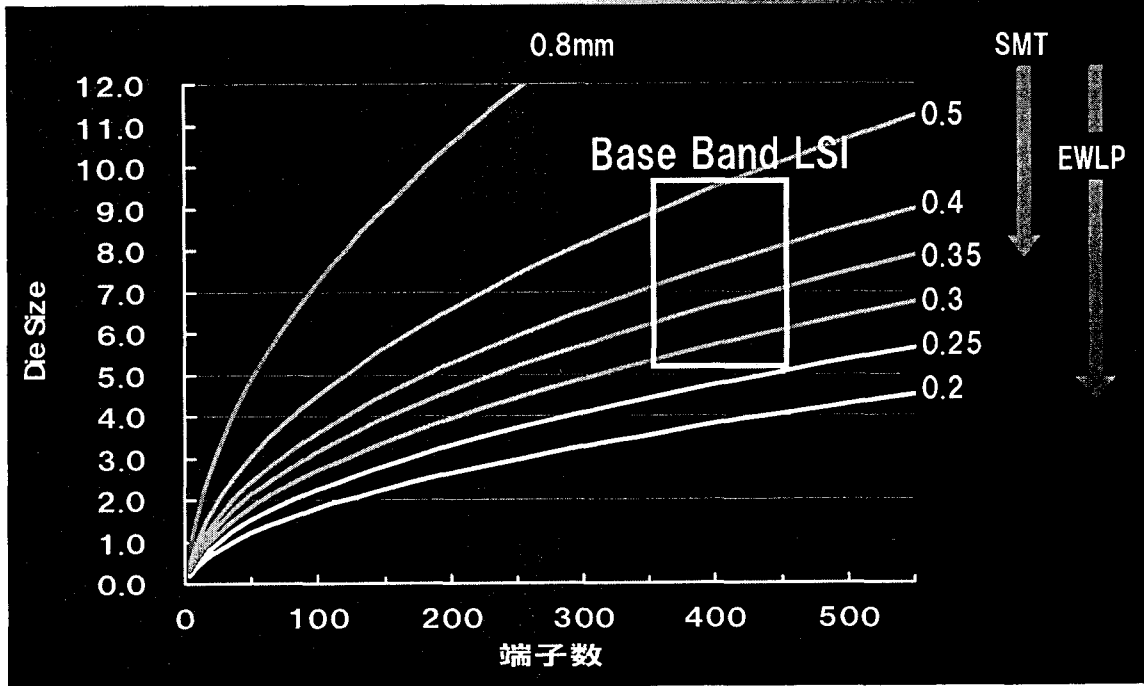
VII Stress Buffer for Low-k Materials

- *Structure and Technology*
 - *Electroplated Copper Post and Encapsulation by Epoxy Material with Filler*
 - *Thickness: 30-90um*
 - *Re-distribution*
 - *Thickness: 5-20um*
- *Purpose*
 - *Low-k, High-k Material Protection against Mechanical Stress*
 - *Mechanical, Thermal Change*
 - *Test Contact*
 - *General Reflow Process in Flip Chip Assembly*
- *Application*
 - *The Leading Edge Semiconductor Chip Assembly*

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Die Size, Number of Balls and Ball Pitch

Page 33



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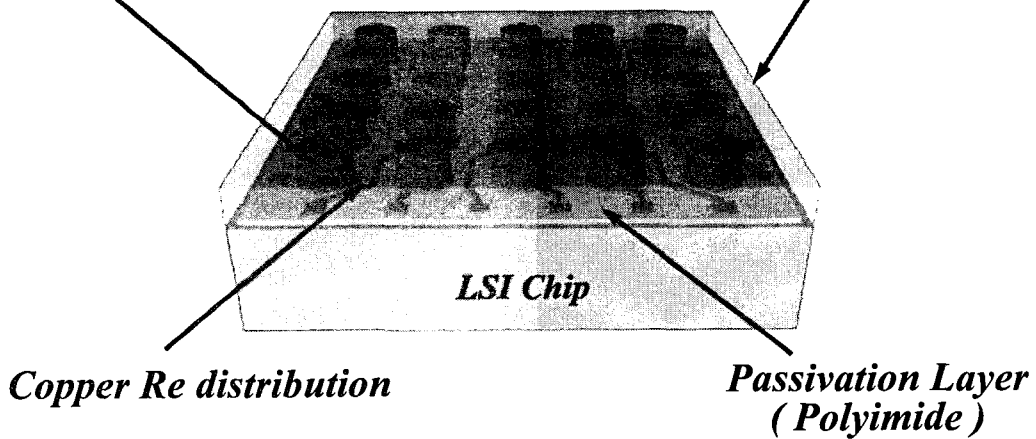
Basic Structure of WLP for "EWLP®"

Page 39

No Solder Ball !

Copper Bump
(Post)

Encapsulation Material
(Epoxy Resin)



Preparing WLP Devices

WLP Placement



Laminate (Hot press Process)



Laser Via Drilling



Subtractive Process

Electro less Copper Plating



Electro Copper Plating



Copper Pattern Photolithography



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EWLP® Process Concept

Page 42

Solder Resist



Terminal Finish (Solder Ball Placement)



Dicing



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EWLP® Module (Multi WLP)

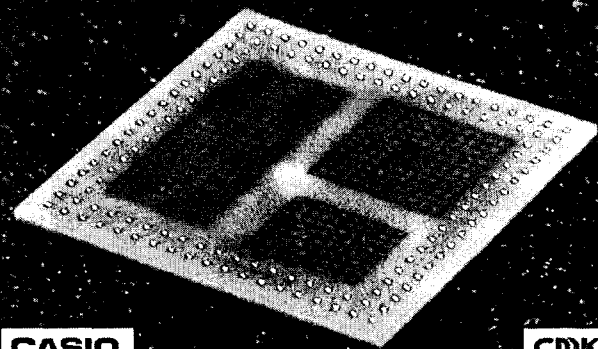
Page 43

- *High Performance Digital Processor Module*
 - *High Speed Signal*
 - *Bus Line*
- *Equivalent to System LSI*
 - *Small Form Factor*
 - *Plane Structure*
- *Copper Interconnect*
 - *High Performance*
 - *Solder Free*



*EWLP® Module
(EWLP® Structure)*

*Large System
Module Structure*



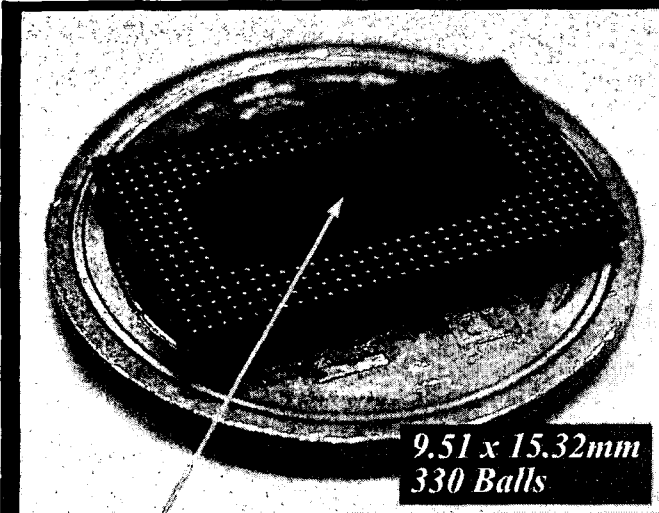
CASIO.

CMK

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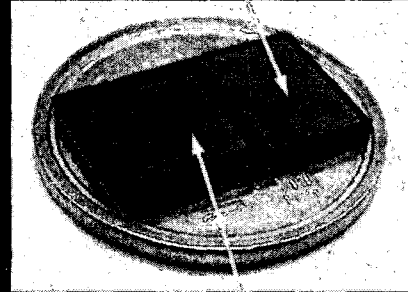
Prototype Sample

Page 44



9.51 x 15.32mm
330 Balls

128 M bit Flash Memory
8.51 x 5.75mm, 48 Balls WLP



128 M bit Mobile DRAM
7.02 x 7.09 mm, 54 Balls, WLP

System LSI

Embedded WLP

5.75 x 5.75 mm, 0.2 mm pitch, 312Pad WLP

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EWLP, WLP & Passive Integrated Module

Page 45



Passives are mounted on EWLP Terminal Side or the other Side

- By Conventional SMT
 - EWLP®, WLP and Passive
 - Flexibility of Mounting
- Passives Devices*

● Analog, RF

- RF Module Application

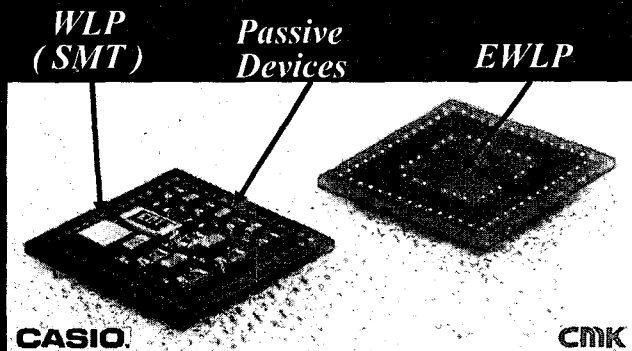
● GSM, Cdma

● Bluetooth, RF LAN

● GPS

● Digital TV Tuner

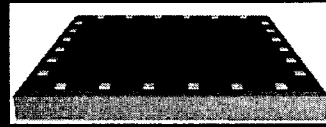
RF Module Mechanical Sample



Bare Die vs. WLP for Embedded Process

Bare Die Issue

- KGD Issue (Good Die)
- Finer Pad Pitch
- Thin film Pad Material
- Difficulty of PCB Process Technology
- Imperfect Reliability



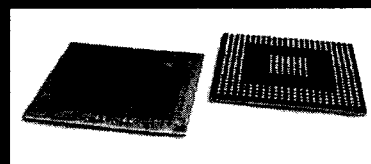
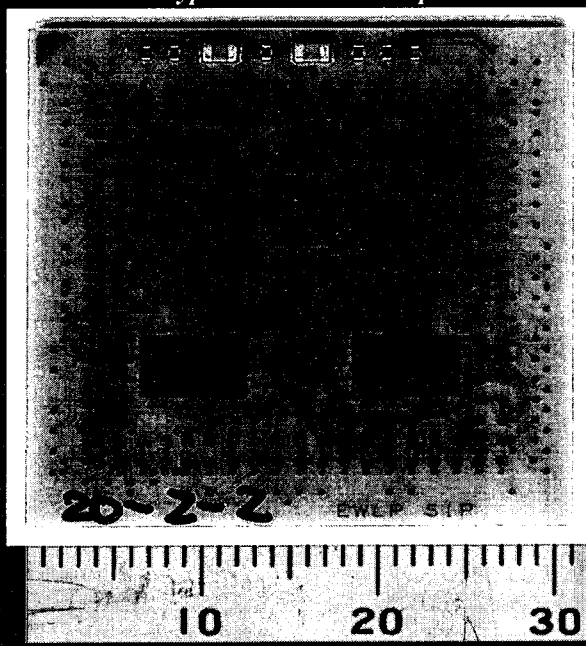
Advantages of WLP Embedded

- + Easy Test and Wafer Level B/I
- + Design Flexibility from WLP Re-distribution
- + Copper Terminal Finish
- + Perfect Protection
- + High Reliability



CPU EWLP® Module (RENESAS, CASIO, CNK)

Prototype Evaluation Sample



CPU(SH4/200MHz)/WLP

- 6.43 x 6.43 mm
- 246+77 copper pads
- 0.2, 0.5 mm pitch

64Mbit SDRAM/WLP

- 3.876 x 6.15 mm
- 91 copper pads (58)
- 0.4 mm pitch

Bus Speed : 100 MHz

EWLP® Module Board

- Size : 31 x 31 mm
- Layer : 2-2-2 Build Up
- L/S : 35/35 --- 50/50 um

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FCBGA, WLPBGA & EWLP®

Page 48

1st Generation
*Conventional C4
(Solder Bump Flip Chip in BGA)*

2nd Generation
WLP

3rd Generation
EWLP®

Mother Board and/or Socket

Interposer *LSI Chip*

- *Fine Solder Bump*
- *Fine Pitch Interconnect*
- *T/C Reliability*
- *Low-k Protection*
- *Fine Pitch Interposer*

*WLP Technology Solution
for High Performance
Device*

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Conclusion (CASIO's WLP & EWLP® Technology)

Page 50

- *Package for Consumer Mobile Products*
 - *Smaller, Thinner Package*
 - *Advanced Module Solution*

- *EWLP® for High Performance Products*
 - *Copper Distribution on Chip*
 - *Low-k Packaging Solution*
 - *“Lead Free!”*
 - *Solder Less Interconnect for High Performance & Reliability*